

Form PTO-1449 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 124418		APPLICATION NO. 10/540,389	
INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)				APPLICANTS Satoshi TAKEI et al.			
				FILING DATE July 20, 2005			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	
<i>Le</i>	1	4,835,089	05/30/1989	Iwayanagi et al.			
	2	5,919,599	07/06/1999	Meador et al.			
	3	5,693,691	12/02/1997	Flaim et al.			
<i>Le</i>	4	6,057,239	05/02/2000	Wang et al.			
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	
<i>Le</i>	5	WO 02/05035 A1 w/abstract	01/17/2002	WIPO			
	6	EP 1 150 343 A2	10/31/2001	Europe			
	7	JP A 2001-83705 w/abstr. + trans.	03/30/2001	Japan			
	8	JP A 2002-47430 w/abstr. + trans.	02/12/2002	Japan			
	9	JP A 48-67447	09/14/1973	Japan			
	10	JP A 61-205494 w/abstract	09/11/1986	Japan			
<i>Le</i>	11	JP A 10-215893 w/abstr. + trans.	08/18/1998	Japan			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)							
<i>Le</i>	12	Lynch et al., "Properties and Performance of Near UV Reflectivity Control Layers," SPIE Vol. 2195, pp. 225-229, 1994					
	13	Taylor et al., "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography," Part of the SPIE Conference on Advances in Resist Technology and Processing XVI, Vol. 3678, pp. 174-185, March 1999					
<i>Le</i>	14	Meador et al., "Recent Progress in 193 nm Antireflective Coatings," Part of the SPIE Conference on Advances in Resist Technology and Processing XVI, Vol. 3678; pp. 800-809, March 1999					
EXAMINER <i>Le</i>				DATE CONSIDERED <i>9/12/06</i>			
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

Date: July 20, 2005